

SPUTTERING TARGET

ABSTRACT

5 Provided is a sputtering target comprising an alloy containing Co or Fe as its main component and an oxide containing Mn and B. The sputtering target is characterized by the composition, which satisfies the condition of $9 \text{ at\%} \leq \text{Mn} + \text{B} + \text{O} \leq 56 \text{ at\%}$, $\text{B} \leq \text{Mn} \text{ (at\%)}$, $\text{Mn} + \text{B} \leq \text{O} \text{ (at\%)}$. The sputtering target of the present invention can inhibit abnormal discharge caused by nonmagnetic materials, which in turn causes the generation of particles during sputtering.

Fig. 1